

Notice of References Cited		Application/Control No.	Applicant(s)/Patent Under Reexamination HOULIHAN ET AL.	
		Examiner Amanda C. Walke	Art Unit 1752	Page 1 of 1

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	C	US-6,875,555	04-2005	Feiring et al.	430/270.1
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NON-PATENT DOCUMENTS

*	Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages	
U	Tran et al., "Metal-Catalyzed Vinyl Addition Polymers for 157nm Resist Applications.2. Fluorinated Norbornenes: Synthesis, Polymerization, and Initial Imaging Results", <i>Macromolecules</i> 35, pp. 6539-6549 (2002).	
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.